

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention	METHOD FOR FORMING NARROW GATE STRUCTURES ON SIDEWALLS OF A LITHOGRAPHICALLY DEFINED SACRIFICIAL MATERIAL
-------------------------------	--

Application Number :

Confirmation Number:

First Named Applicant: Bruce Doris

Attorney Docket Number: FIS920040036US1

Art Unit:

Examiner:

Search string: (6638810 or 6383872 or 6391525).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
<i>AK</i>	1	6638810	2003-10-28	BAKLI, ET AL.			
<i>AK</i>	2	6383872	2002-05-07	KADOSH, ET AL.			
<i>AK</i>	3	6391525	2002-05-21	LYONS			

Signature

	Examiner Name		Date
---	---------------	--	------

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

ATTY DOCKET NO.

FIS920040036US1

SERIAL NO.

10/709,314

BRUCE B. DORIS ET AL.

FILING

4/28/04

GROUP

MAY 26 2004

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	1	S. Deevi and Z. A. Munir; "The Mechanism of Synthesis of Titanium Nitride by Self-Sustaining Reactions;" Journal of Materials Research Society, Vo. 5, No. 10, October 1990; pages 2177 - 2183.
	2	J. Hartmann, W. ensinger, A. Koniger, B. Stritzker, and B. Rauschenbach; "Formation of Titanium Nitride Coatings by Nitrogen Plasma Immersion Ion Implantation of Evaporated Titanium Films;" Journal of American Vacuum Society Technology, A 14(6); November/December 1996; pages 3144 - 3146.

EXAMINER

DATE CONSIDERED

9/30/05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

(Use several sheets if necessary)

SERIAL NO.
10/709,314

FILING
4/28/04

GROUP




U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO

OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*

	3	Y. L. Zou, T. L. Alford, Y. Zeng, F. Deng, S. S. Lau, T. Laursen, A. I. Amali, and B. M. Ullrich; "Formation of Titanium Nitride by Annealing Ag/Ti Structures in Ammonia Ambient;" Journal of Applied Physics Vol. 82, (7).1; October 1997; pages 3321 - 3327.
	4	M. F. C. Willemsen, A. E. T. Kuiper, A. H. Reader, R. Hokke, and J. C. Barbour; "In Situ Investigation of TiN Formation of Top of TiSi ₂ ;" Journal of Vacuum Science Technology, B6(1), Jan/Feb 1988; pages 53 - 61
EXAMINER 		DATE CONSIDERED 9/30/05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

ATTY DOCKET NO.
FIS920040036US1

SERIAL NO.
10/709,314

BRUCE B. DORIS ET AL.

FILING
4/28/04

GROUP



U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	5	Y. Takahashi, H. Ishii, and J. Murota; "New Platinum Silicide Formation Method Using Reaction Between Platinum and Silane;" Journal of Applied Physics, 58 (8), 15 October 1985; pages 3190 - 3194.
	6	S. Hymes, Sp. P. Murarka, C. Shepard, and W. A. Lanford; "Passivation of Copper by Silicide Formation of Dilute Silane;" Journal of Applied Physics, 71 (9), 1 May 1992; pages 4623 - 4625

EXAMINER

DATE CONSIDERED

9/30/05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

ATTY DOCKET NO.
FIS920040036US1

SERIAL NO.
10/709,314

BRUCE B. DORIS ET AL.

FILING
4/28/04

GROUP




U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	7	S. Humes, K.S. Kumar, S.P. Murarka, P. J. Ding, W. Wang, and W.A. Lanford; "Thermal Stability of Copper Silicide Passivation Layers in Copper-Based Multilevel Interconnects;" Journal of Applied Physics, Vo. 83, No. 9, April 15, 1998; pages 4507 - 4512
	8	L. H. Dubois and R.G. Nuzzo; "Reactivity of Intermetallic Thin Films Formed by the Surface Mediated Decomposition of Main Group Organometallic Compounds;" Journal of Vacuum Science Technologies, A2 (2), April - June 1984; pages 441 - 445.
EXAMINER 	DATE CONSIDERED 9/30/05	

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

(Use several sheets if necessary)

SERIAL NO.
10/709,314

BRUCE B. DORIS ET AL.

FILING
4/28/04

GROUP



U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
.							
.							
.							
.							

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	9	L. Dubois and R. Nuzzo; "The Decomposition of Silane and Germane on Ni(111): Implications for Heterogeneous Catalysis;" Surface Science 149; 1985; pages 133 - 145
	10	T. Abe, Y. G. Hong, M. Esashi; "Highly Selective Reactive-Ion Etching Using CO/NH3/Xe Gases for Microstructuring of Au, Pt, Cu, and 20% Fe-Ni;" Journal of Vacuum Science Technology, B21(5), Sept/Oct 2003; pages 2159 - 2162

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION
(Use several sheets if necessary)

Docket Number (Optional)

FIS920040036US1

Application Number

10/709,314

Applicant(s)

Bruce B. Doris et al.

Filing Date

4/28/04

Group Art Unit

*EXAMINER
INITIAL

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

N. Matsui, K. Mashimo, A. Egami, A. Konishi, O. Okada, T. Tsukada; "Etching Characteristics of Magnetic Materials (Co, Fe, Ni) Using CO/NH3 Gas Plasma for Hardening Mask Etching;" Vacuum 66, 2002; pages 479 - 485

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.